

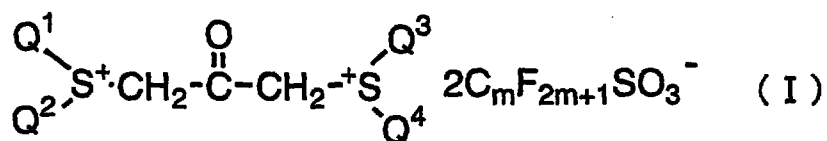
ABSTRACT

CHEMICAL AMPLIFICATION TYPE POSITIVE RESIST COMPOAITIONS AND SULFONIUM SALTS

A chemical amplifying type positive resist composition having high transmittance, superior in sensitivity and resolution in a lithography utilizing a light having a wavelength of 220 nm or lower and conferring a good profile is provided,

Which comprises

an aliphatic sulfonium salt represented by the following formula (I):



wherein either Q^1 , Q^2 , Q^3 and Q^4 represent an alkyl group or a cycloalkyl group, or Q^1 and Q^2 and/or Q^3 and Q^4 form, together with the adjacent sulfur atom, a heterocyclic group, and m represents an integer of 1 to 8;

at least one onium salt selected from the group consisting of a triphenylsulfonium salt and a diphenyliodonium salt; and a resin which contains a polymerization unit having a group unstable to an acid, and which is insoluble in alkali by itself but becomes soluble in alkali by the action of an acid.